

Title (en)

MIRROR, IN PARTICULAR FOR A MICROLITHOGRAPHIC PROJECTION EXPOSURE APPARATUS

Title (de)

SPIEGEL, INSBESONDERE FÜR EINE MIKROLITHOGRAPHISCHE PROJEKTIONSBELICHTUNGSANLAGE

Title (fr)

MIROIR, EN PARTICULIER POUR APPAREIL D'EXPOSITION PAR PROJECTION MICROLITHOGRAPHIQUE

Publication

EP 4193222 A1 20230614 (EN)

Application

EP 20760779 A 20200807

Priority

EP 2020072214 W 20200807

Abstract (en)

[origin: WO2022028709A1] The invention relates to a mirror, in particular for a microlithographic projection exposure apparatus. A mirror according to the invention has an optical effective surface (101, 201, 301), a mirror substrate (110, 210, 310, 410), a reflection layer system (120, 220, 320) for reflecting electromagnetic radiation that is incident on the optical effective surface (101, 201, 301), at least one actuator layer which is configured to transmit an adjustable mechanical force on the reflection layer system (120, 220, 320), thereby producing a locally variable deformation of the optical effective surface (101, 201, 301), and at least one cooling device configured to at least partially dissipate heat generated by said actuator layer.

IPC 8 full level

G03F 7/20 (2006.01)

CPC (source: EP)

G03F 7/70266 (2013.01); **G03F 7/70316** (2013.01); **G03F 7/70891** (2013.01)

Citation (search report)

See references of WO 2022028709A1

Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)

BA ME

Designated validation state (EPC)

KH MA MD TN

DOCDB simple family (publication)

WO 2022028709 A1 20220210; CN 115997170 A 20230421; EP 4193222 A1 20230614; TW 202210953 A 20220316

DOCDB simple family (application)

EP 2020072214 W 20200807; CN 202080104190 A 20200807; EP 20760779 A 20200807; TW 110126938 A 20210722